

METHODS AND SYSTEMS TO COMPENSATE FOR A
STITCHING DISTURBANCE OF A PRINTED PATTERN IN A
MASKLESS LITHOGRAPHY SYSTEM NOT UTILIZING OVERLAP OF
THE EXPOSURE ZONES

ABSTRACT

A method and system are provided for forming a pattern within an area of a photosensitive surface. An exemplary method includes performing a first exposure of the photosensitive surface in accordance with predetermined image data, wherein the first exposure occurs during a first pass and produces a first image within the area. The image data is adjusted to compensate for identified image deficiencies image deficiencies, the image deficiencies being within a region of the first image. A second exposure, of the photosensitive surface, is performed in accordance with the adjusted image data during a second pass.